

New 400 V SiC MOSFET technology delivering highest efficiency in three-level industrial drive applications

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Presentation outline





- Introduction of the 400 V CoolSiC™ Trench MOSFET technology
- 400 V CoolSiC[™] MOSFET properties and benefits
- Device performance in 3-Level ANPC inverter
 - Outlook: device performance in 3-Level PFC
- Summary and Conclusion



Introduction of the 400 V CoolSiC[™] Trench MOSFET technology

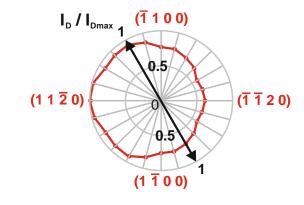
Silicon-carbide is not Silicon Device design addresses material-specific properties

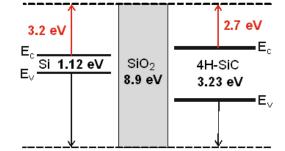
- epitaxial layers must be grown off-axis to gain sufficient control of the doping level
- this leads to a rough surface and a mix of different crystal faces with different properties
 - use a trench rather than a planar gate and align to an undisturbed crystal face
- hexagonal lattice leads to anisotropic crystal properties

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- as consequence channel mobility, threshold voltage, interface charge density depend on the crystal plane
 - ➡ use asymmetric channel and align to a-plane for high channel mobility
- SiC shows larger Fowler-Nordheim tunneling through gate oxide due to the larger bandgap of SiC
- breakdown in SiC occurs at much higher electric fields, causing also higher fields and consequently shorter oxide lifetime of the gate oxide
 - → p+ type shielding regions below the trench limit electric field in the gate oxide

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4° off-axis

wafer surface

<1120>

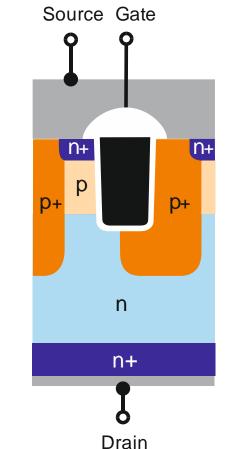
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400 V Cell design

- the 400 V SiC MOSFET cell structure is based on the design of the already released higher voltage classes (as depicted exemplary)
- the significant performance improvements are gained by
 - further reduced cell pitch
 - refined channel properties
 - enhanced control over drift region properties

Built on continouos technology advancements

- optimization of chip design to minimize losses of active area





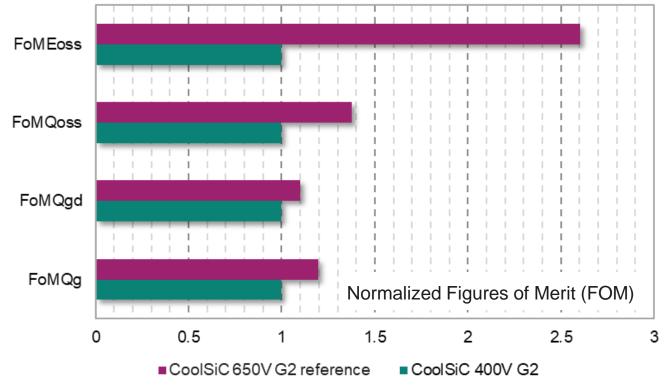


400 V CoolSiC[™] MOSFET properties and benefits



Excellent switching FOMs

- optimization of CoolSiC G2 for a lower breakdown voltage of 400 V results in excellent FoM improvements compared to the 650 V reference
- CoolSiC 400V G2 is the best-fit for a wide range of applications, including 3L-ANPC inverters for drives and solar or AI Server PSUs, with bus voltages of ≤ 300 V in 2L topologies and ≤ 600 V in 3L topologies

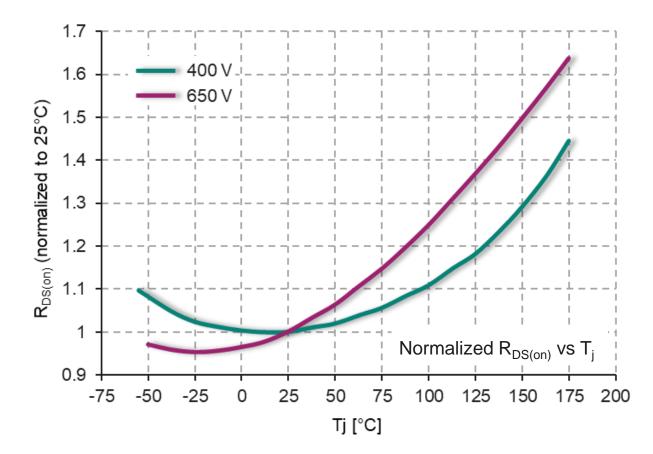


FOMs defined at V_{DS} = 200 V for 400 V SiC and at V_{DS} = 400 V for 650 V SiC reference part

Flat temperature dependence of on-resistance



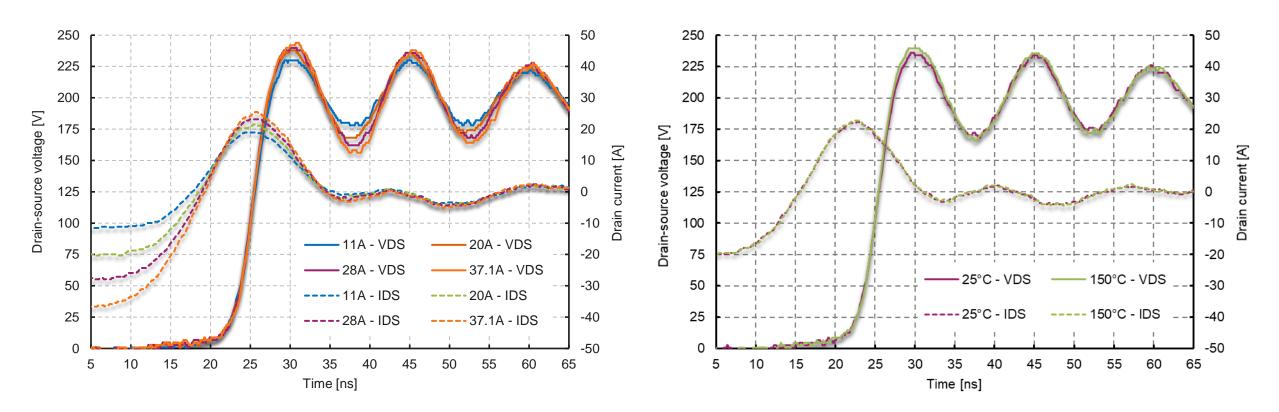
- the on-resistance of the 400 V device increases only by 11% with temperature rise from 25°C to 100°C
- flat R_{DS(on)} vs T_j characteristics enables the use of MOSFETs with higher R_{DS(on),typ}, which is linked to lower costs and better switching performance



Commutation ruggedness of body diode



- double pulse characterization of 11 m Ω device (IMT40R011M2H)
- device shows stable switching waveforms with small overshoots and little ringing
- commutation behavior is almost independent of load current and operating temperature



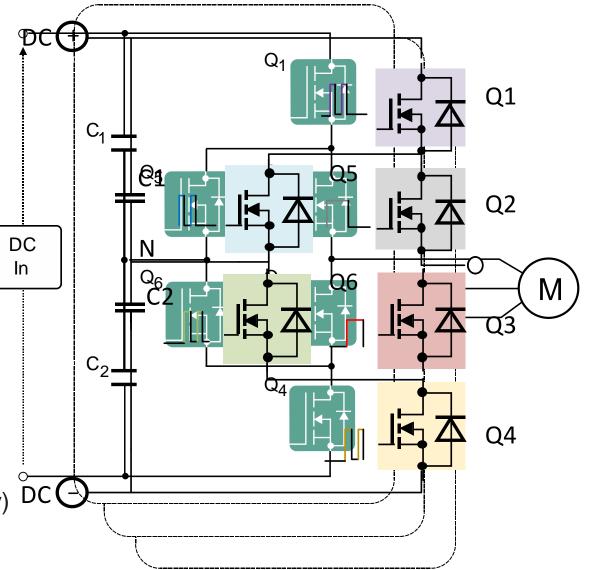


Device performance in 3-Level ANPC inverter



What is 3-Level ANPC topology

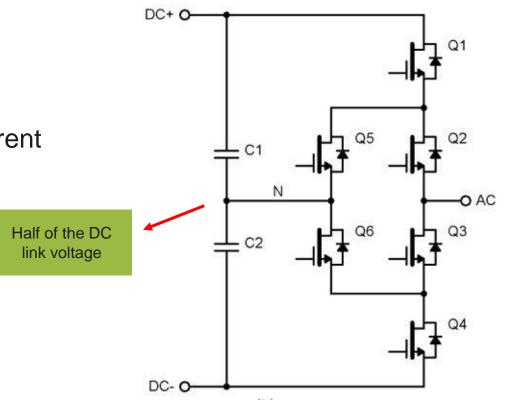
- 3L ANPC (Three Level Active Neutral Point Clamp) is a bidirectional topology
- it allows usage of half DC link voltage semiconductor devices since a DC Capacitor Bank divides the DC link voltage
- there are 3 different modulation schemes possible
- LF Modulation is selected because of the uniform temperature between MOSFETs and easier layout
- Q2 and Q3 are switching at low frequency while Q1, Q4,
 Q5, Q6 are modulated at carrier frequency (high frequency)





Benefits of 3-Level ANPC

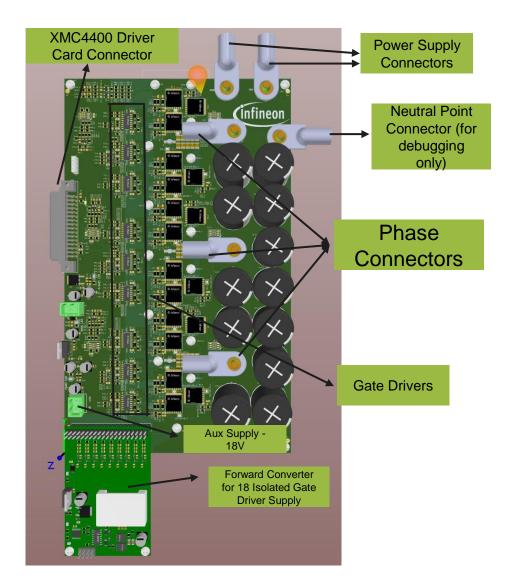
- lower voltage rated semiconductors
- better switching performance due to lower voltages
- better EMI performance due to slower dv/dt and three different voltage levels
- better conduction performance due to lower voltages
- better efficiency
- higher output power





Introduction of the test board

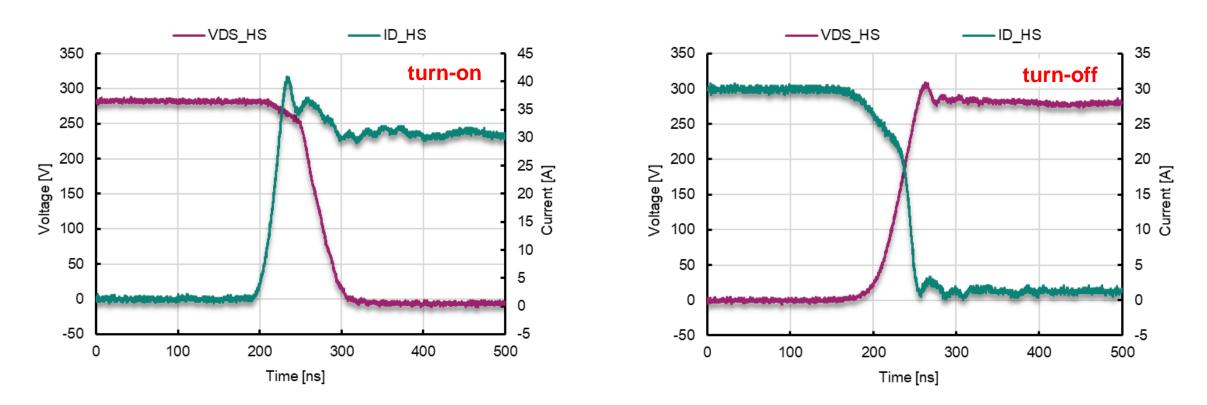
- 18 x SiC 400V IMT40R01XM2H in TOLL package
- 4 Layer 2oz, 1.76mm thickness PCB
- 9x 2EDF7275 gate driver
- Forward Converter for gate driver supply
 - 1 Input 18 Isolated Outputs with planar transformer
 - XMC1302-T028 for communication and controlling
 - OptiMOS BSZ099N06LS5 60 V in half bridge configuration
 - 2EDF7275 gate driver with bootstrap
- 3x TLI4971 current sensor to measure the output phase current



Switching waveforms



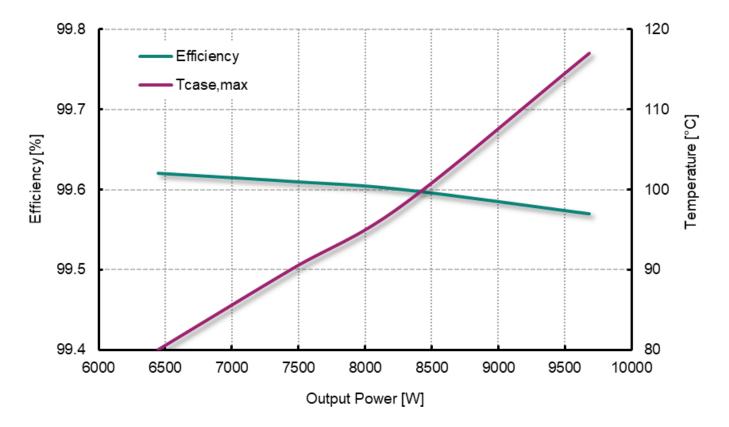
- switching waveforms were measured using a double-pulse configuration of the 3-Level ANPC board
- use of an inductive-resistive load of 1 mH + variable resistance
- the dv/dt per switch is limited to 5 V/ns
- measurements reveal a very smooth switching behavior of the 400 V device





Efficiency and case temperature

- inverter runs at a switching frequency of 10 kHz, dv/dt per switch limited to 5 V/ns, V_{DC} = 600 V
- no heatsink connected to enable temperature measurement by a thermal camera
- efficiency analysis excludes gate drivers and controller stage
- inverter delivers an efficiency of η = 99.57 % for 9.74 kVA load



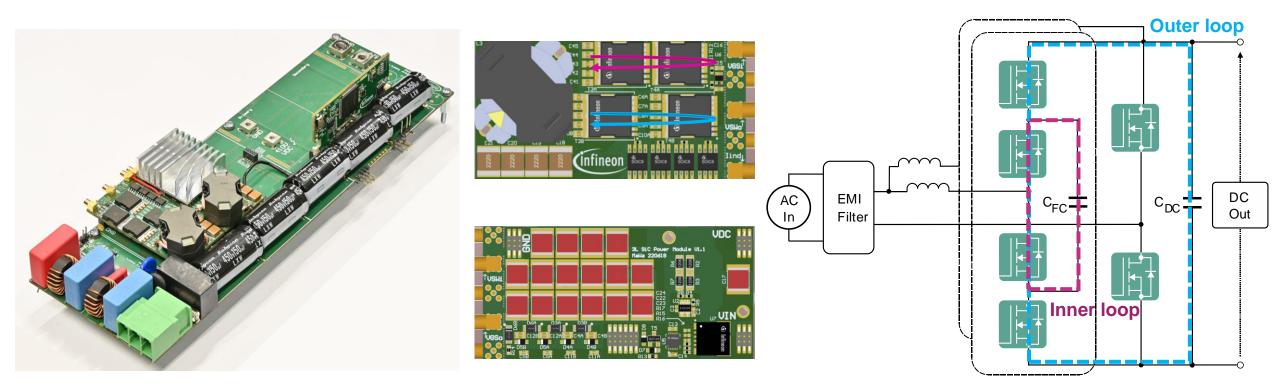


Outlook: device performance in 3-Level PFC

Technology demonstrator platform

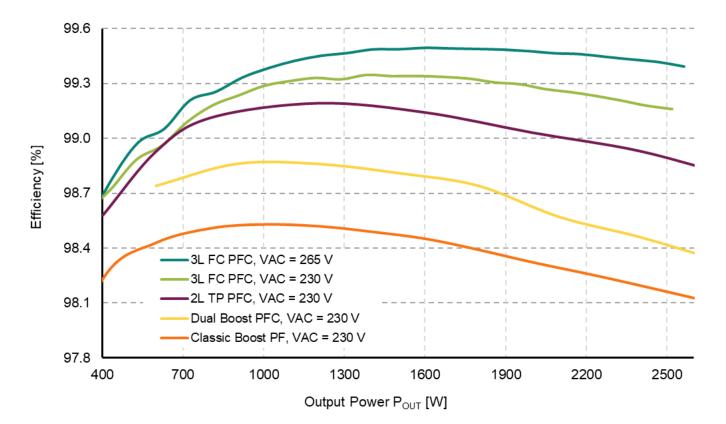


- 2x interleaved 3-Level Flying-Cap (FC) PFC, each leg capable of 2.5 kW output power
- switching frequency of 80 kHz at device level results in 320 kHz effective for significant smaller EMI
- 230 VAC input and above, DC link voltage of 380 V or 420 V depending on input voltage





- the 3-Level FC solution outperforms the 2-Level TP PFC at an AC input voltage of 230 V, resulting in 25% lower losses
- the series connection of 2x 400 V devices allows also higher input levels of 277 VAC or even 350 VAC, which helps to address the increasing power demand of AI in data centers









Summary

- the new 400 V CoolSiC[™] G2 MOSFET technology is introduced, which offers a unique combination of performance, reliability and ease of use
- it offers Ron x A reduction and FOM improvement over existing solutions, with flat R_{DS,on} vs T_J characteristics
- the low charges and the linearity of the output capacitance offer fast-switching capability, high slew rate control and low EMI
- the new devices allow highest efficiency and power density by enabling the adoption of innovative topologies, like 3-Level ANPC or 3-Level PFC
- the advantages of the new devices are demonstrated in a medium-power 3-phase 3-Level ANPC inverter
- the superior inverter efficiency beyond 99.5% (at dv/dt ≤ 5 V/ns) confirms the expected potential of the technology
- the high potential of the 400 V SiC MOSFET technology is also confirmed by the test results in a 3-Level Flying-Capacitor PFC



Thank you for the attention!

I'm pleased to answer your questions. owen.song@infineon.com